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PATENT APPLICATION

Docket Number: 081468-0309012 Client Reference: P-1840.000-US_

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IN THE UNITED STATES, PASENT AND TRADEMARK OFFICE

In Re the Application of

ZAAL et al.

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Group Art Unit: 2812

Application No.: 10/814,815

Examiner: Unassigned

Filed: April 1, 2004

Confirmation No.: 5302

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

September 7, 2004

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

1105 2011/105	Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
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`,	DR	DE SMIT (081468-0309173)	10/820,227	04/08/2004	 ☑ Specification ☑ Drawings ☑ Other: stamped receipt card
		DE SMIT (081468-0309978)	10/860,662	06/04/2004	☑ Specification☑ Drawings☑ Other: stamped receipt card
\mathcal{N}		DUINEVELD et al. (081468-0308101)	10/773,461	02/09/2004	☑ Specification☑ Drawings☑ Other: stamped receipt card
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'n×		DE SMIT et al. (081468-0306530)	10/705,804	11/12/2003	⊠ Specification ⊠ Drawings ⊠ Other: stamped receipt card
		LOF et al. (081468-0306781)	10/705,805	11/12/2003	☑ Specification☑ Drawings☑ Other: stamped receipt card
	D.R.	LOF et al. (081468-0306524)	10/705,783	11/12/2003	☑ Specification☑ Drawings☑ Other: stamped receipt card

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•	Examiner's	First Inventor	Application	Filing	Enclosed
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	SEP 1 200 3	VAN SANTEN et al. (081468-0307331)	10/743,271	12/23/2003	☑ Specification☑ Drawings☑ Other: stamped receipt card
Review	\$ 5/	MULKENS et al. (081468-0307333)	10/743,266	12/23/2003	 ☑ Specification ☑ Drawings ☑ Other: stamped receipt card
Review Dist		DERKSEN et al. (081468-0306526)	10/705,785	11/12/2003	Specification Drawings Other: stamped receipt card
		SIMON et al. (081468-0307087)	10/724,402	12/01/2003	Specification Drawings Other: stamped receipt card
		BLEEKER (081468-0306527)	10/715,116	11/18/2003	☑ Specification☑ Drawings☑ Other: stamped receipt card
00 Va		STREEFKERK et al. (081468-0306882)	10/719,683	11/24/2003	☑ Specification☑ Drawings☑ Other: stamped receipt card
No X		LOF et al. (081468-0306525)	10/705,816	`11/12/2003	☑ Specification☑ Drawings☑ Other: stamped receipt card
' X		DIERICHS (081468-0308270)	10/775,326	02/11/2004	☒ Specification☒ Drawings☒ Other: stamped receiptcard
•	·	LOF et al. (081468-0309957)	10/857,614	06/01/2004	Specification Drawings Other: stamped receipt card
		SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	☑ Specification☑ Drawings☐ Other: stamped receipt card
	D.R.	KOLESNYCHENHO et al. (081468-0309196)	10/823,777	04/14/2004	☑ Specification☑ Drawings☑ Other: stamped receipt card

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

<u>PLEASE DO NOT PRINT</u> the above information on the patent which results from this application.